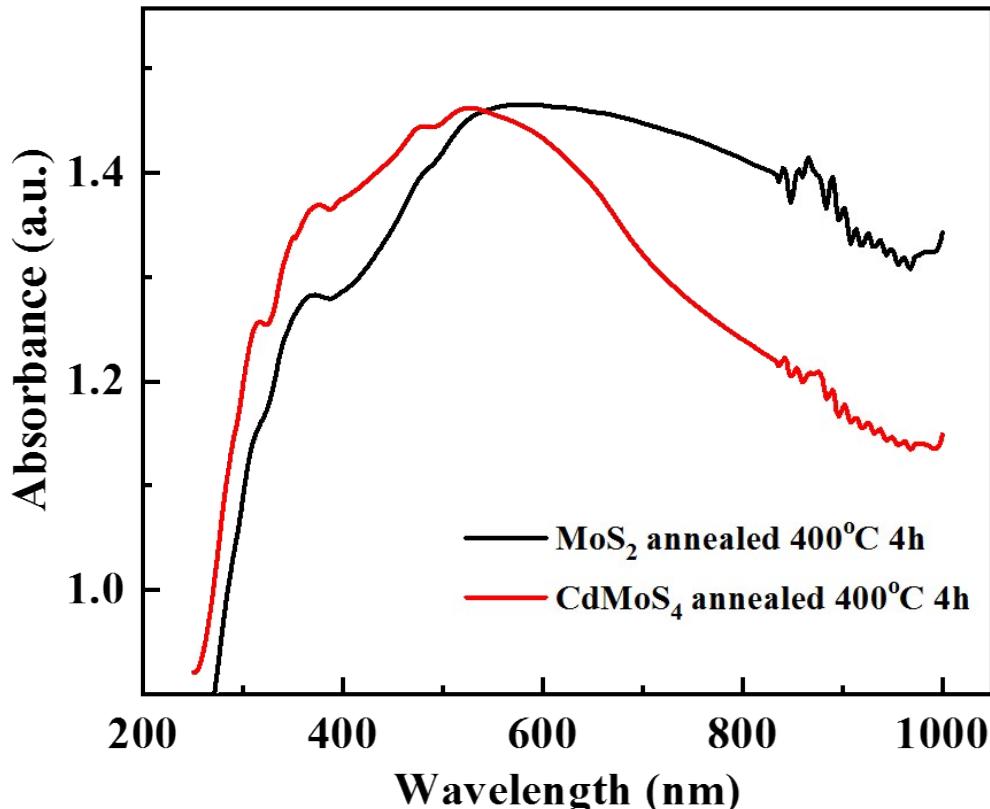


## **Supplementary Material**

### **MoS<sub>2</sub> and CdMoS<sub>4</sub> nanostructures based UV light Photodetector**

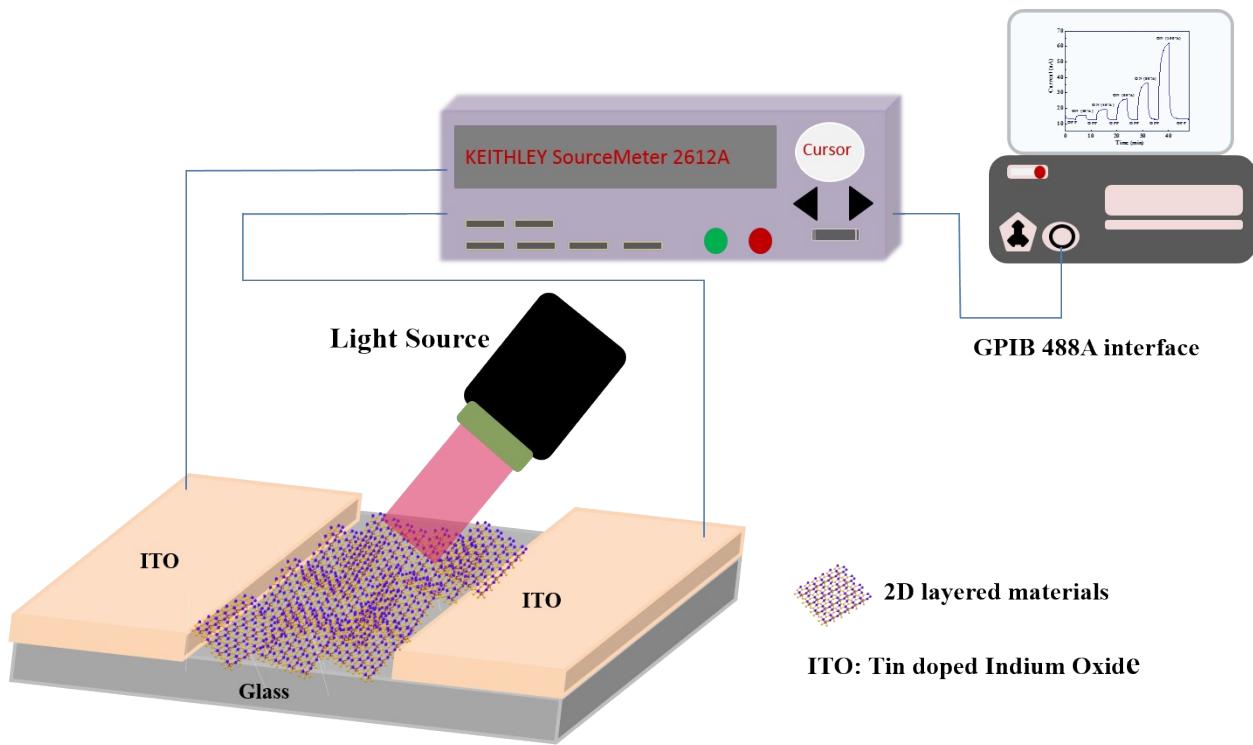
Mahendra S. Pawar,<sup>a,b</sup> Sunil R. Kadam,<sup>c</sup> Bharat B. Kale,<sup>\*c</sup> Dattatray J. Late<sup>\*,a,b,d</sup>

**Fig. S1**



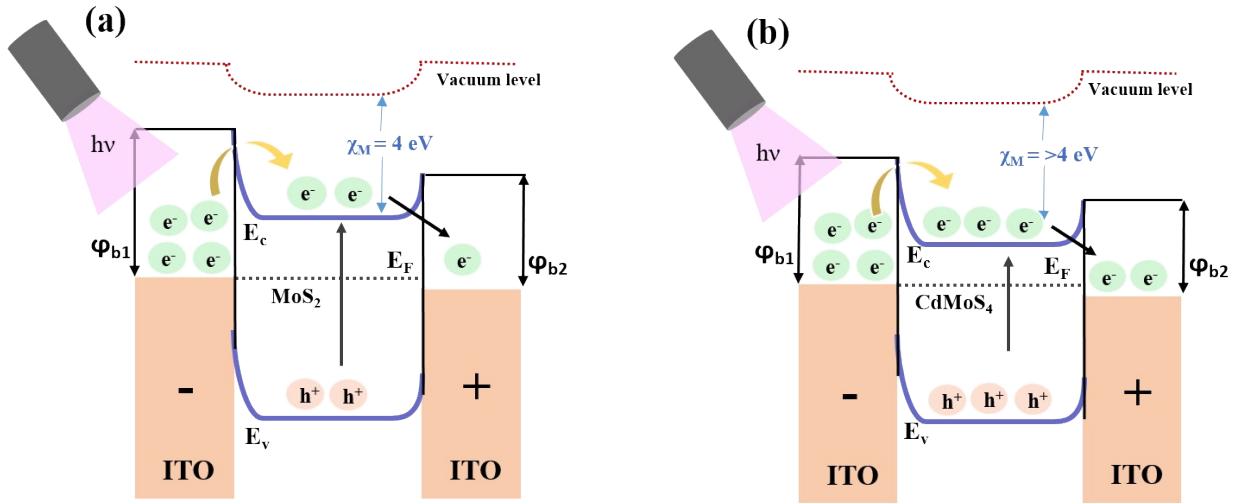
**Fig. S1** UV-Visible spectra for MoS<sub>2</sub> (Black color) and CdMoS<sub>4</sub> (Red color) samples annealed at 400°C.

**Fig. S2**



**Fig. S2** Schematic of the Experimental setup for measurement of UV light Photodetector.

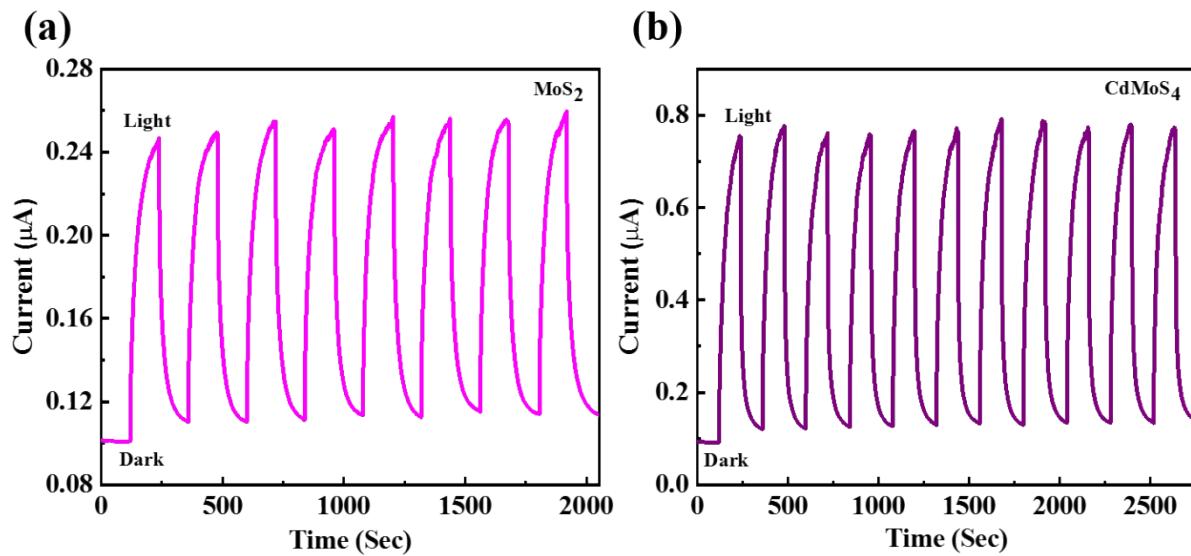
**Fig. S3**



**Fig. S3** Energy band diagram for (a) MoS<sub>2</sub> and (b) CdMoS<sub>4</sub> using ITO electrode under biasing and light illumination conditions.

Photodetector mechanism under biasing and light illuminations using ITO electrode: The fig.S4 shows the energy band diagram for the Schottky barrier (ITO/MoS<sub>2</sub>) and (ITO/CdMoS<sub>4</sub>) in the photodetector device under biasing and light illumination conditions. The parameters such as  $\varphi_b$  (4.7 eV),  $\chi_M$  (4 eV),  $\varphi_{b1}$  and  $\varphi_{b2}$  are the workfunction of the ITO electrode, electron affinity of the MoS<sub>2</sub>, schottky barrier height at the ITO/MoS<sub>2</sub> and ITO/CdMoS<sub>4</sub> respectively.<sup>1</sup> When light falls on the device under biasing conditions electrons from the ITO layer will start crossing the schottky barrier ( $\varphi_{b1}$ ). Once the barrier is crossed due to thermionic field emission it easily crosses the lower schottky barrier ( $\varphi_{b2}$ ), further these electrons are collected at the positively biased Ito electrode. In case of CdMoS<sub>4</sub> the barrier height is lower compared to MoS<sub>2</sub> hence it results in the generation and collection of charge carriers. This gives rise to enhancement in the photocurrent value also the photoresponsivity.

**Fig. S4**



**Fig. S4** Cyclic photo response study on (a)  $\text{MoS}_2$  and (b)  $\text{CdMoS}_4$  samples annealed at  $400^\circ\text{C}$ .

**Table. 1**

Material	Spectral Range (nm)	Responsivity	Response Time	Recovery Time	Ref
MoS <sub>2</sub>	1550	47.5 mA/W	10 ms	16 ms	2
MoS <sub>2</sub> /Black Phosphorous	1550	153.4 mA/W	15 µs	70 µs	3
Bilayer MoS <sub>2</sub>	1070	5.2 A/W	44.5 s	404.7 s	4
rGO/MoS <sub>2</sub>		2.1 A/W	18 ms		5
MoS <sub>2</sub>	637	~1 A/W	64 µs	51 µs	6
MoS <sub>2.19</sub>	THz radiation	10 mA/W	5.12 s	6.33 s	7
Few layer MoS <sub>2</sub>	532	~20 mA/W	12 s	19 s	8
MoS <sub>2</sub> /CsPbBr <sub>3</sub>	442	4.4 A/W	0.72 ms	1.01 ms	9
MoS <sub>2</sub> /CdTe	780	36.6 mA/W	43.7 µs	82.1 µs	10
MoS <sub>2</sub>	365	3 * 10 <sup>4</sup> A/W	32 ms		11
MoS <sub>2</sub>	385	0.41 µAcm <sup>2</sup> /W	118 s	123 s	This work
CdMoS <sub>4</sub>		4 µAcm <sup>2</sup> /W	74 s	94 s	

**Table 1:** Comparative photodetector performance of the MoS<sub>2</sub> and CdMoS<sub>4</sub> to the previously reported Mo based photodetector devices.**References:**

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